

Asian Module

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No news from the last meeting

except minor update of beam test result

typical performance meets ILD requirement $100\mu\text{m}$ σ_{rphi} , 5% dE/dx

some behavior are still not explained well

such as

diffusion constant are not stable in each pad row

angular dependence is not understood well . . .

Module does has not been updated more than 10 years

(except minor modification of GEM)

It's almost time to renew , under common module design concept

how ?

Asian module

concept : minimize dead region with Gate device

Frame less @ module side -> effect is unclear

we may have dead area even without frame

due to gap btw module (1mm clearance in design)

GEM hole cannot be allocate the edge

local dead area @module boundary might be miner thing

comparing to “aligned” module EP design

would be proposed by Mech. session

for deformation

Concept of Asian GEM module LP1

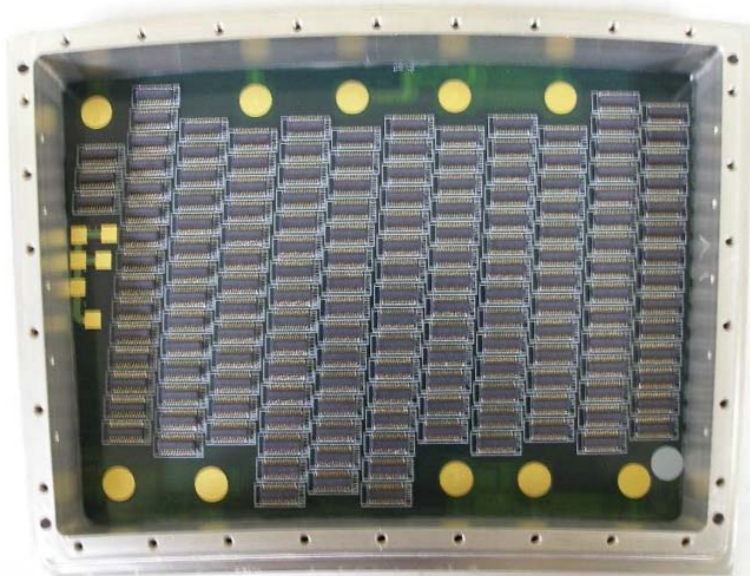
Pad plane (w/ Tsinghua U.)

pad pitch ~1.1mm

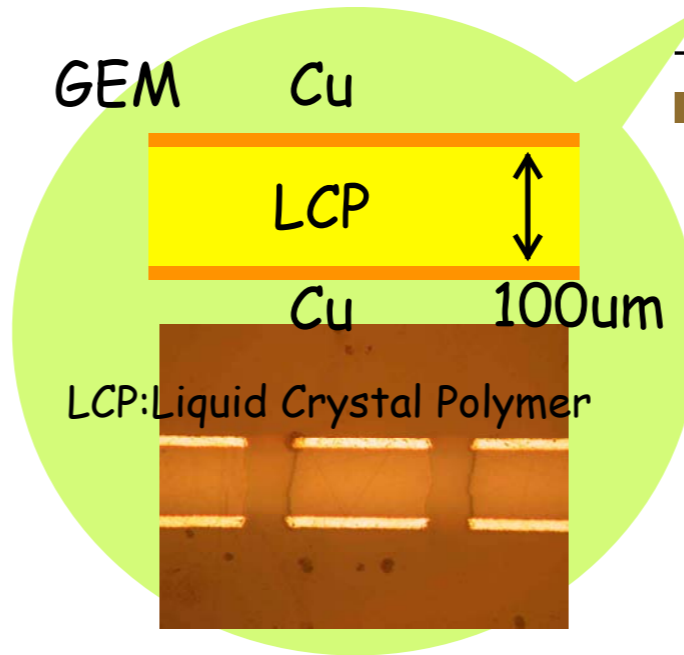
pad height ~5.5mm

by ~300um diff.@amp.GEM

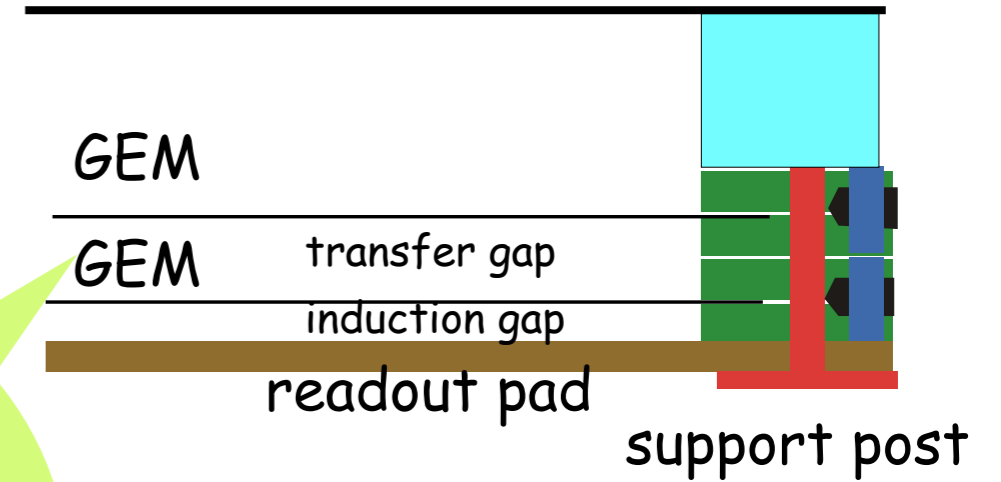
~5000 pads/module



connectors cover most of the area in backside



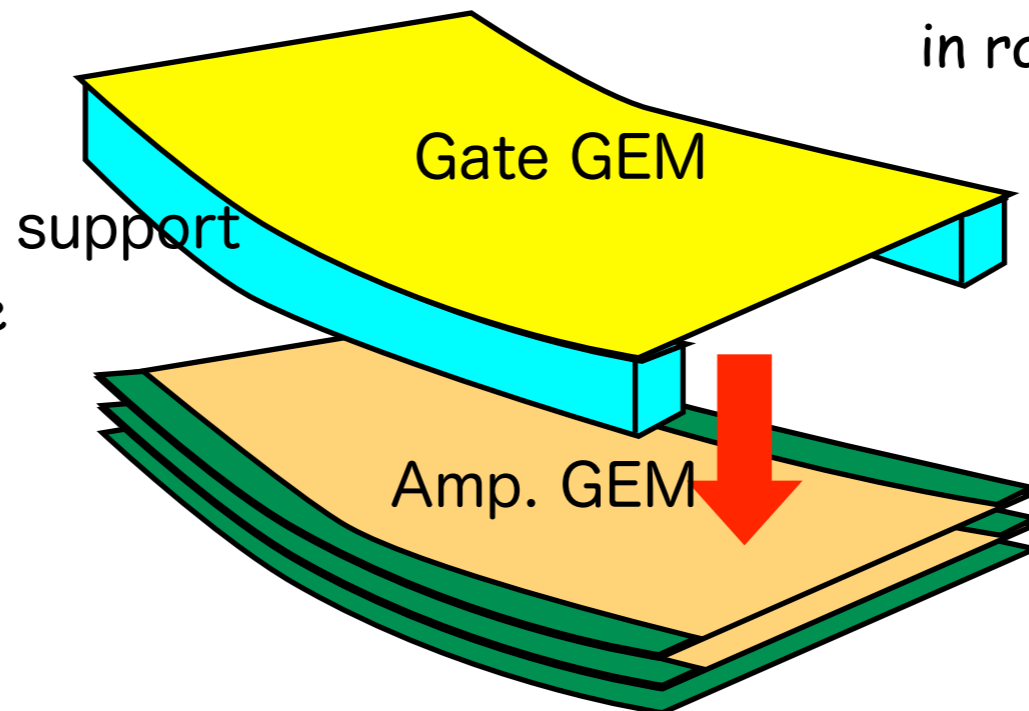
14um Gate GEM



Amp. structure

Double 100um thick GEM

GEM stretched by support post to minimize dead(support) area in radial direction



GEM gate

14um thick GEM

Upper structure of module (Amp. GEM + Gate)

Which kind of GEM is the best for ILC ?

we have been waiting ideal GEM coming but ????????

std GEM, LCP GEM, teflon GEM,

glass GEM

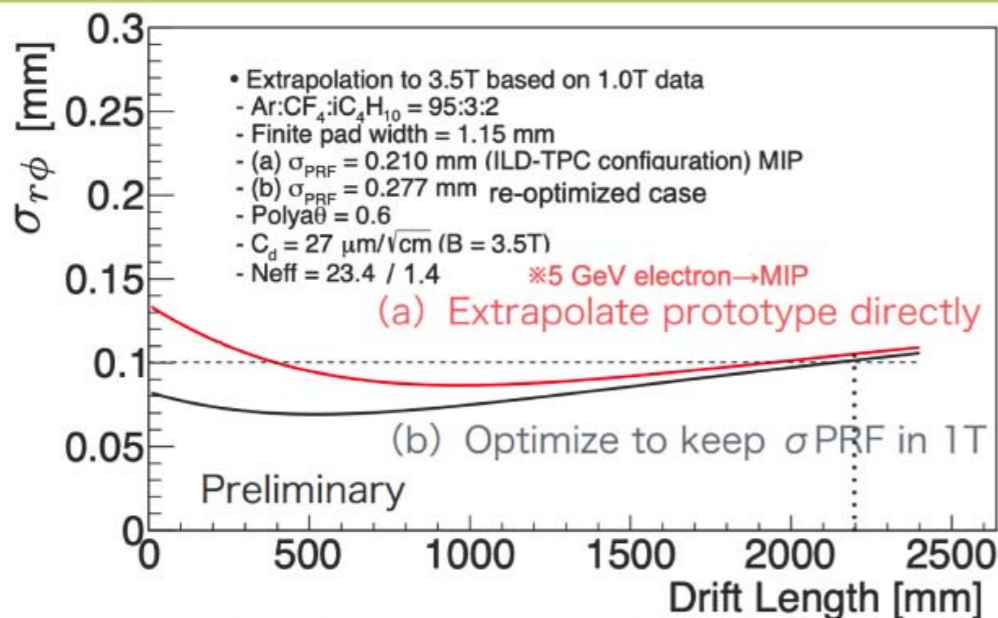
ceramic GEM

these are rigid, no frame is necessary (?)

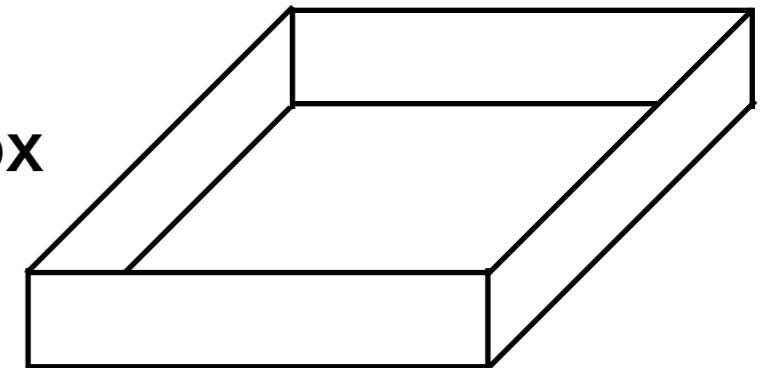
but GATE must be thin, so frame is necessary

Extrapolation of spatial resolution

11



rigid box



How do we enlarge diffusion at amp. region
 current 6mm(4mm trans. + 2mm indu.)
 should be 8mm??
 or other ? method

When we decide hit points by center of gravity, the graph is (a) because of bias.

When we optimize to keep σ_{PRF} in 1T, we get graph (b)
 \rightarrow The spatial resolution (100 μm) can be achieved

Middle structure of module (PCB)

front side

Pad plane : 1mm width?

routing

rear side

connectors

current connector

X-talk btw neighbor channel >10%

not necessary to be high pitch like we used at LP1

-> Saclay's connector

can we make it 3 times more dense ?

RO chip can be mounted 5000ch on one side?

how to cooperate w/ sAltro16 effort

Back structure of module (electronics+cooling) must be same

Gate: this is not a specific issue of Asian module

Gate R&D with FUJIKURA

type0 -> type3 (current final model for 10x10cm size)

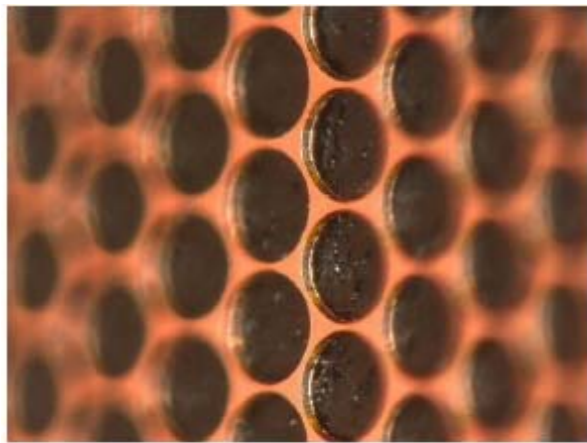
type4 is module size

type4 is produced @2015

some production@2016 for beam test

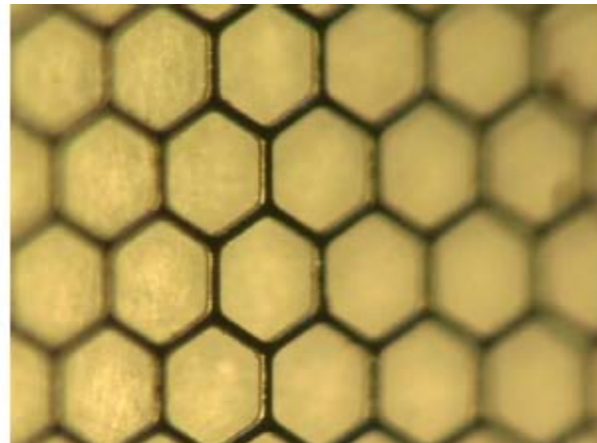
but no further production is done.

we may need to make sure their technology still alive someday



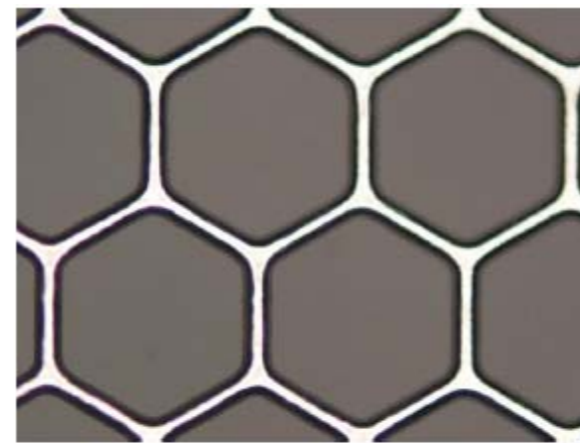
Gate GEM Type 0

形状:丸穴
穴径:300 μ m
リム幅:top 15 μ m, bottom 30 μ m
開口率:75%
size : 10 x10 mm
Process : Lazer direct



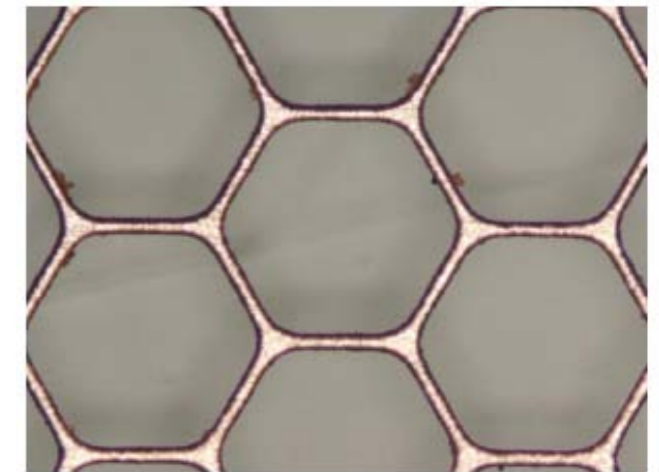
Gate GEM Type 1

形状:ハニカム
穴径:295 μ m
リム幅:top 25 μ m, bottom 35 μ m
開口率:80%
size : 30 x30 mm
Process : Ni -Plating



Gate GEM Type 2

形状:ハニカム
穴径:275 μ m
リム幅:top 35 μ m, bottom 40 μ m
開口率:76%
size : 90 x90 mm
Process : Ni-Plating



Gate GEM Type 3

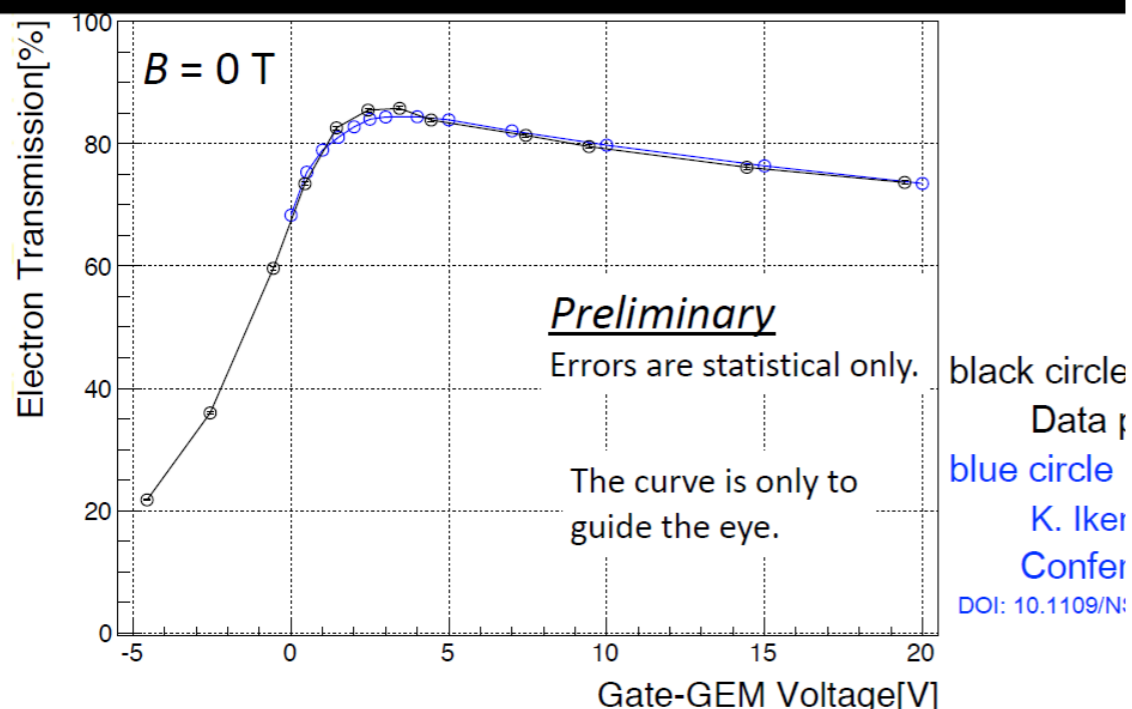
穴径:295 μ m
リム幅:top 10 μ m, bottom 25 μ m
開口率:85%
size : 30 x30 mm
Process : Ni-less-Process

Electron transmission has been measured
 by using test chamber with std 10x10cm GEM
 with 3GEM, with 2GEM and ? with MM ? using Fe
 by LP1 module w/ Asian module using ^{55}Fe , Laser and Beam

Transmission are obtained by different methods
 but obtained results agree well each other (within error)
 from charge ratio, position resolution and dE/dx

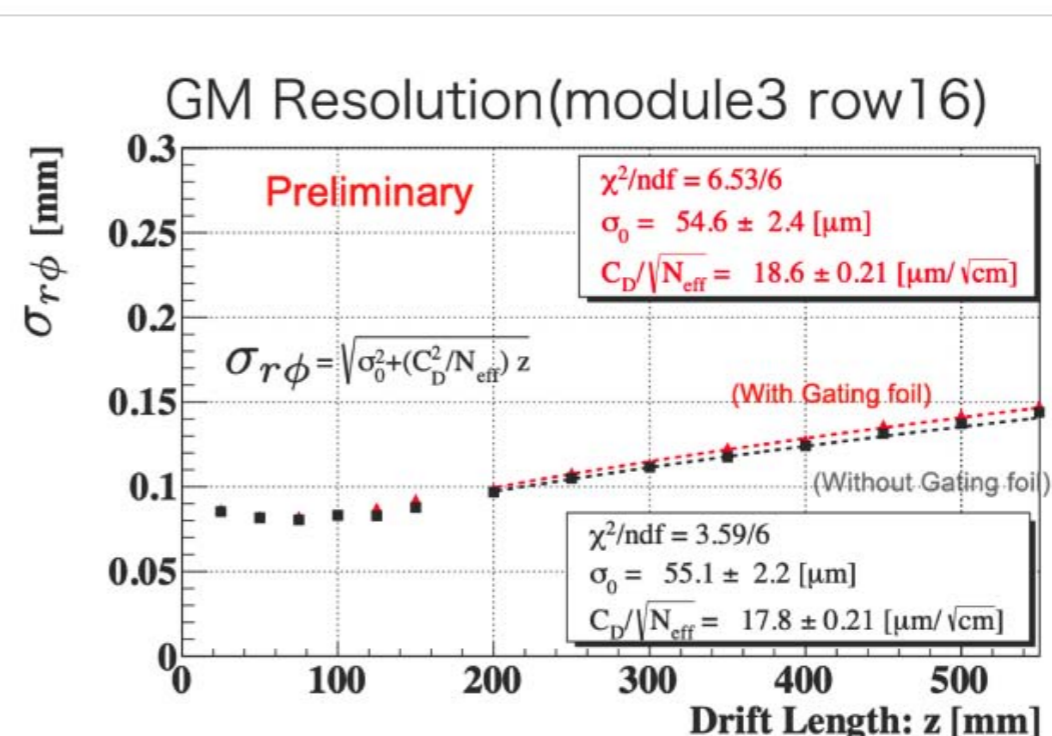
Quality Gate seem to be same for different sample

Electron transmission rate vs. ΔV measured with ^{55}Fe



- The maximum transmission rate is about 86% at around $\Delta V = +3.5 \text{ V}$.
- The transmission rate decreases slowly above $+3.5 \text{ V}$.
- It decreases rapidly with increasing negative ΔV .
- The measurement is difficult below $\Delta V = -4.5 \text{ V}$ because of small signals.

Spatial resolution



Track angle cut[deg]
 (With Gate)
 $-4.49 < \phi_{\text{loc}} < 0.0$

(Without Gate)
 $-6.78 < \phi_{\text{loc}} < -2.7$

Transmission is also measured by CERN with P. Colas
show similar results with different gas Ar/CO₂ with 3GEM

they also measure ion back flow using ⁵⁵Fe

we don't see any problem yet

Basic performance of Fujikura Gate meets our requirements !
can be a primary candidate for Gate

WP5 mission is completed ?

What do we do next ?

a proof of 10⁻⁴ reduction of ions at closed gate

real module design/fabrication/HV supply

Summary

We have to consider what will we do
after Green(?) light on

we should summarize

what would be integrated in common module

from past studies

what would be studied individually in each module